



THW 2818

[10191/4116]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : LAERMER et al.
Serial No. : 10/524,610
Filed : August 11, 2005
For : LAYER SYSTEM HAVING A SILICON LAYER AND A PASSIVATION LAYER, METHOD FOR CREATING A PASSIVATION LAYER ON A SILICON LAYER AND ITS USE
Art Unit : 2818
Examiner : HO, Hoang Quan Tran
Confirmation No. : 9981
Customer No. : 26646

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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Date: October 11, 2006

Signature:

Jong H. Lee (R. No. 36,197)

RESPONSE TO RESTRICTION REQUIREMENT

SIR:

In response to the requirement for restriction contained in the Office Action dated September 15, 2006, Applicants elect Invention I (claims 16-28) directed to a layer system, for further prosecution on the merits.

Respectfully submitted,

KENYON & KENYON LLP

(R. NO. 36,197)

Dated: October 11, 2006

By: JONG LEE to Gerard Messina
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